

Form PTO-1449
(Rev. 2-32)U.S. Department of Commerce
Patent & Trademark OfficeAtty. Docket No.
005329 ALRT/MASK/RTSerial No.
UNKNOWNINFORMATION DISCLOSURE STATEMENT
(Use several sheets if necessary)Applicant:
Shirley HEMAR et al.Filing Date:
Concurrently herewith

Group

J1017 U.S. PTO
09/876955

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Sub-Class	Filing Date (if appropriate)
JS	6,016,357	1/18/00	Neary et al.	382	144	1/16/97
JS	5,795,688	8/18/98	Burdorf et al.	430	30	8/14/96
JS	6,072,898	6/6/00	Beaty et al.	382	146	6/16/98
JS	6,148,097	11/14/00	Nakayama et al.	382	141	6/5/96
JS	6,075,883	6/13/00	Stern et al.	382	144	11/12/96
JS	6,025,905	2/15/00	Sussman	356	3.01	12/31/96
JS	6,052,478	4/18/00	Wihl et al.	382	144	10/9/96
JS	6,018,392	1/25/00	Tzu et al.	356	351	10/23/98
JS	6,081,659	6/27/00	Garza et al.	395	500.22	4/26/99
JS	6,078,738	6/20/00	Garza et al.	395	500.22	5/8/97

FOREIGN PATENT DOCUMENTS

Document	Date	Country	Class	Sub-class	Translation Yes/No
JS 0 628 806 A2	12/14/94	Europe			

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

JS	Budd, Russell A., et al., "A New Tool for Phase Shift Mask Evaluation, the Stepper Equivalent Aerial Image Measurement System - AIMS TM ," SPIE Vol. 2087 Photomask Technology and Management (1993).
JS	Schenker, Richard, "Comparison of Single and Dual Exposure Phase Shift Mask Approaches for Poly Gate Patterning," SPIE, Vol. 3546, September 1998.

EXAMINER

John Strege

DATE CONSIDERED

6/3/04

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication.

Form PTO-1449
(Rev. 2-32)U.S. Department of Commerce
Patent & Trademark OfficeINFORMATION DISCLOSURE STATEMENT
(Use several sheets if necessary)Atty. Docket No.
005329 ALRT/MASK/RTSerial No.
UNKNOWNApplicant:
Shirley HEMAR et al.Filing Date:
Concurrently herewith

Group

U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Sub-Class	Filing Date (if appropriate)
JS	5,745,168	4/28/98	Ninomiya	348	191	
JS	5,744,381	4/28/98	Tabata et al.	438	16	
JS	5,481,624	1/2/96	Kamon	382	144	
JS	5,441,834	8/15/95	Takekuma et al.	430	5	
JS	5,272,116	12/21/93	Hosono	437	228	
JS	4,922,308	5/1/90	Noguchi et al.	356	237	
JS	4,148,065	4/3/79	Nakagawa et al.	358	101	
JS	5,572,598	11/5/96	Wihl et al.	382	144	
JS	6,091,845	7/18/00	Pierrat et al.	382	144	2/24/98

FOREIGN PATENT DOCUMENTS

Document	Date	Country	Class	Sub-class	Translation Yes/No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER

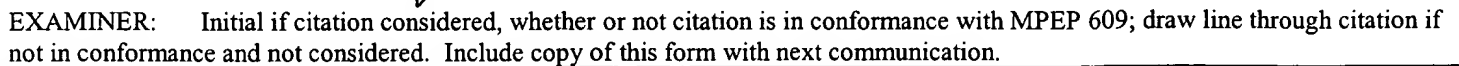
John H. Cooper

DATE CONSIDERED

6/3/04

EXAMINER:

Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication.



**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

Complete if Known

Application Number	09/876,955
Confirmation Number	4359
Filing Date	June 7, 2001
First Named Inventor	Shirley HEMAR
Art Unit	2623
Examiner Name	J. Mancuso
Attorney Docket Number	005329 USA/MASK/RT/OR

Sheet	1	of	1
-------	---	----	---

Examiner Initials*	Cite No. ¹	Document Number		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
		Number	Kind Code ² (if known)		
JS		US 5,965,306	A	10-12-1999	Mansfield et al.
JS		US 6,335,129	B1	01-01-2002	Asano et al.
JS		US 5,576,829	A	11-19-1996	Shiraishi et al.
JS		US 5,795,688	A	08-18-1998	Burdorf et al.
JS		US 2002/0171825	A1	11-21-2002	Krantz et al.
		US			
		US			
		US			
		US			

[illegible]

Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city, and/or country where published.	Translation ⁶
JS		Budd et al., "A New Mask Evaluation Tool, The Microlithography Simulation Microscope Aerial Image Measurement System," <i>Optical / Laser Microlithography</i> 7, San Jose, March 2-4, 1994, Proceedings of SPIE, Optical/Laser Microlithography, Bellingham, SPIE, US Vol. 2197, pages 530-540.	
JS		Martino et al., "Application of the Aerial Image Measurement System (AIMS) to the Analysis of Binary Mask Imaging and Resolution Enhancement Techniques," <i>Optical / Laser Microlithography</i> 7, San Jose, March 2-4, 1994, Proceedings of SPIE, Optical/Laser Microlithography, Bellingham, SPIE, US Vol. 2197, pages 573-584.	

John Stree

5/3/04

¹ Applicant's unique citation designation number (optional). ² See Kind Codes of USPTO Patent Documents at www.uspto.gov, MPEP 901.04 or in the comment box of this document. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST. 3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to indicate here if English language Translation is attached.